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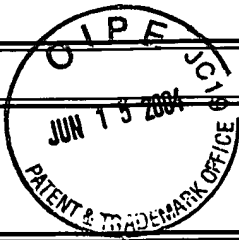
Electronic Filing System (EFS) Data
Electronic Patent Application Submission
USPTO Use Only

EFS ID: 62626
Application ID: 09912844
Title of Invention: HIGH PRESSURE PROCESSING CHAMBER
FOR SEMICONDUCTOR SUBSTRATE
First Named Inventor: Maximilian Biberger
Domestic/Foreign Application: Domestic Application
Filing Date: 2001-07-24
Effective Receipt Date: 2004-06-15
Submission Type: Information Disclosure Statement
Filing Type:
Confirmation number: 5915
Attorney Docket Number: NONE



Total Fees Authorized:

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Electronic Version v1.1
Stylesheet Version v1.1.0

Title of Invention

HIGH PRESSURE PROCESSING CHAMBER FOR SEMICONDUCTOR
SUBSTRATE

Application Number: 09/912844
Date: 2001-07-24
First Named Applicant: Maximilian A. Biberger

Confirmation Number: 5915
Attorney Docket Number:



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Submitted by:	Elec. Sign.	Sign. Capacity
Thomas B. Haverstock Registered Number: 32571	/tbh/	Attorney

Documents being submitted
us-ids

Files
SSI00501-usidst.xml
us-ids.dtd
us-ids.xsl

Comments

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

HIGH PRESSURE PROCESSING CHAMBER FOR SEMICONDUCTOR SUBSTRATE

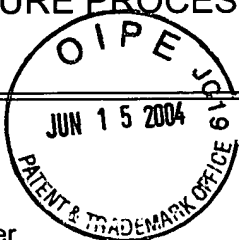
Application Number: 09/912844

Confirmation Number: 5915

First Named Applicant: Maximilian Biberger

Attorney Docket Number:

Search string: (5186594 or 5769588 or 5906866 or 5975492 or 6122566 or 6355072 or 6454519).pn.



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That no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing the certification after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the information disclosure statement.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	5186594	1993-02-16	Toshima et al.			
	2	5769588	1998-06-23	Toshima et al.			
	3	5906866	1999-05-25	Webb			
	4	5975492	1999-11-02	Brenes			
	5	6122566	2000-09-19	Nguyen et al.			
	6	6355072	2002-03-12	Racette et al.	B1		
	7	6454519	2002-09-24	Toshima et al.	B1		

Signature

Examiner Name	Date